

**A B S T R A C T****[Abstract of the Disclosure]**

A metal-insulator-metal (MIM) capacitor is provided. The MIM capacitor includes an upper electrode, a lower electrode, and a dielectric layer interposed between the upper and lower electrodes. A first voltage is applied to the upper electrode, and a second voltage is applied to the lower voltage. A wiring layer for applying the first voltage to the upper electrode is formed on a lower level than or on the same level as the lower electrode. Therefore, it is possible to minimize the thickness of the dielectric layer as much as possible while maintaining the reliability of the dielectric layer to some extent. Therefore, it is possible to realize a MIM capacitor having a high capacitance.

**[Representative Drawing]**

15 FIG. 3

**[Indexes]**

MIM Capacitor, High Capacitance, Contact Hole